



Mr. Jung-youl Lee

(DONGJIN SEMICHEM, Korea)

Jung-youl Lee is an engineer at Dongjin Semichem, specializing in the development of EUV underlayers and process materials. Recently, he has been researching EUV underlayers and process materials to address various issues that arise during the implementation of EUV patterns.

Before developing the EUV underlayer, he conducted research and developed products aimed at improving the performance of process materials used in semiconductor processes, including ArF BARC and KrF BARC. He also engaged in research on various semiconductor process materials, including the development of neutral layers used in one of the next-generation lithography processes, Direct Self-Align (DSA).

He holds a Bachelor's degree in Chemistry and a Master's degree in Polymer Chemistry from Kwangwoon University.